

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-893001	Application No. 10/789,670
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Arun Ramamoorthy et al.	
		Filing Date February 27, 2004	Group Art Unit 1724

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AQ	Chauhan, M.M., et al., "Photoresist Outgassing in EUV", 2000 March Meeting: <i>Bulletin of the American Physical Society</i> , 45(1):563, abstract #L36.112, March 2000.
	AR	Moors, R., et al., "Electrostatic mask protection for extreme ultraviolet lithography", <i>Journal of Vacuum Science & Technology B: Microelectronics and Nanometer Structures</i> , 20(1):316-320, Jan/Feb 2002.
	AS	
	AT	

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	